

Gasonics L3300

The Gasonics L3300 plasma system is designed for ashing and cleaning semiconductor wafers. Gasonics L3300 does this by creating monatomic oxygen, the active specie, which chemically reacts with the photoresist on the surface of the wafer.

[Description](#)

Description

Model: Gasonics L3500 Asher semiconductor process equipment

Category: [Plasma Asher](#)

Original Equipment Manufacturer: [Gasonics](#)

Robot upgrade: HINE Hatm 5.0 atmospheric robot arm

Wafer Size: 6 inch configuration.

Process Gasses: O2 and N2

estimated weight: 200kg